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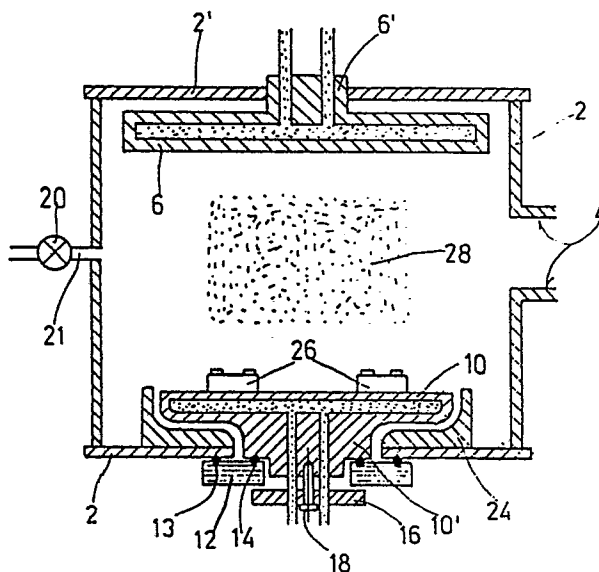
71 Applicant: **SELENIA INDUSTRIE ELETTRONICHE
ASSOCIATE S.p.A., Via Tiburtina, KM 12.400,
I-00131 Roma (IT)**

72 Inventor: **Misiano, Carlo, Via G.B. Morgagni, 22,
I-00161 Roma (IT)**
Inventor: **Simonetti, Enrico, Piazza della Radio, 14,
I-00146 Roma (IT)**

54 Adjustment to desired value (trimming) on thin film resistors by ion sputtering.

57 A technique for adjusting to the desired value, thin film integrated resistors is made known. This method consists in exposing a resistor (26) whose thickness is greater than that necessary for the desired resistance, to ionic sputtering of the resistive material until the resistor thickness is such as to correspond to the desired electric resistance.

Ion-sputter etching is realised either by means of a plasma (28) or by means of an ion-gun (34).



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DOCUMENTS CONSIDERED TO BE RELEVANT			
Category	Citation of document with indication, where appropriate, of relevant passages	Relevant to claim	CLASSIFICATION OF THE APPLICATION (Int. Cl. 3)
X	FR-A-2 354 617 (SOCIETE FRANCAISE DE L'ELECTRO-RESISTANCE) *Page 4, line 7 to page 9, line 15; claims 1-3,5,8; figures 4-6*	1,3	H 01 C 17/24
X	DE-A-2 144 656 (HOTTINGER BALDWIN MESSTECHNIK GmbH) *Page 3, last paragraph; claims; figure*	1-3	
A	FR-A-2 253 280 (HEWLETT-PACKARD) *Claims; figure*	1,2	
A	FR-A-2 111 511 (WESTERN ELECTRIC) *Claims; figure*	1,3	
			TECHNICAL FIELDS SEARCHED (Int. Cl. 3)
			H 01 C
The present search report has been drawn up for all claims			
Place of search THE HAGUE		Date of completion of the search 29-03-1983	Examiner GORUN M.
CATEGORY OF CITED DOCUMENTS			
X : particularly relevant if taken alone Y : particularly relevant if combined with another document of the same category A : technological background O : non-written disclosure P : intermediate document		T : theory or principle underlying the invention E : earlier patent document, but published on, or after the filing date D : document cited in the application L : document cited for other reasons & : member of the same patent family, corresponding document	